



**FOR IMMEDIATE RELEASE**

**D2S CHIEF PRODUCT OFFICER LEO PANG NAMED A SPIE FELLOW**

*Dr. Pang recognized by SPIE for his outstanding achievements and contributions to the optics community, including the introduction of curvilinear ILT to the semiconductor lithography and photomask industries*

**SAN JOSE, Calif., February 7, 2023**—D2S, a supplier of GPU-accelerated solutions for semiconductor manufacturing, today announced that Dr. Linyong (Leo) Pang, chief product officer and executive vice president at D2S, has been recognized as a Fellow by SPIE, the international society for optics and photonics. Each year, the SPIE Fellows program recognizes members of the society who have made significant scientific and technical contributions in the fields of optics, photonics and imaging. Dr. Pang will formally accept the honor at the SPIE Advanced Lithography + Patterning Conference to be held in San Jose later this month.

Dr. Pang is most widely known as an icon of curvilinear inverse lithography technology (ILT, an acronym he coined), which he introduced to the lithography and photomask world, and dedicated more than 20 years to advocating and pushing the technology and ecosystem for its adoption. ILT is now a key lithography technology that has been used in the manufacturing of leading-edge chips to improve process window and yield.

Among his many accomplishments at D2S, Dr. Pang led the development and adoption of the industry's only GPU-accelerated mask data preparation (MDP) and mask process correction (MPC) solutions, as well as the development and adoption of a new generation of ILT – the industry's first GPU-accelerated, full-chip, stitchless, curvilinear ILT product. Prior to D2S, he founded and was the general manager of the Computational Lithography division of Luminescent (acquired by Synopsys in 2012) as well as the Computational Metrology and Inspection division of Luminescent (acquired by KLA-Tencor in 2014). His pioneering work in the EDA and semiconductor industries began more than two decades ago at Numerical Technologies, where he invented the company's i-Virtual Stepper system.

Dr. Pang has provided significant service to SPIE. He has served on the conference program committee for the SPIE Photomask Technology Conference, as session and section chair for the SPIE Photomask Technology Conference and the Photomask Japan Conference, as associate editor of the Journal of Micro/Nanopatterning, Materials, and Metrology (JM3), as well as guest editor for JM3's Deep Learning Special Edition and upcoming Curvilinear Masks Special Edition. In addition, he has presented papers at nearly every SPIE Advanced Lithography Conference and Photomask Technology conference since 2001, including a paper co-authored with Micron on D2S' GPU-accelerated curvilinear ILT technology, which was named the winner of the best presentation award (second place) at the Photomask Technology and EUV Lithography Conference in 2019. He was elected a SPIE Senior Member in 2022.



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Dr. Pang has also provided significant service to the optics and semiconductor communities in addition to SPIE. For more than a decade, he has served as co-chair and chair of the Lithography Symposium for the China Semiconductor Technology International Conference (CSTIC), organized by SEMI and IEEE. He has also previously served as Computational Lithography session chair and program chair for the Lithography Workshop.

To date, Dr. Pang has 38 issued patents, 27 pending patents and 85 publications. He received his Ph.D. in mechanical engineering and an additional M.S. in computer science from Stanford University.

According to Aki Fujimura, CEO of D2S, “We give our hearty congratulations to Leo for this honor and recognition from the SPIE community. He’s been a consummate contributor to SPIE. He’s always thinking about how to bring people in the community together to collaborate, not just to improve the state of the art together, but to enjoy each other’s company as we build a stronger bond throughout the industry.”

For more information about the SPIE Fellows program, visit <https://spie.org/membership/member-recognition/spie-fellows/>.

**About D2S**

D2S is a supplier of GPU-accelerated solutions for semiconductor manufacturing. The company provides simulation-based custom solutions to leading equipment partners and D2S TrueMask® solutions to photomask and wafer manufacturers. D2S TrueMask solutions use the D2S Computational Design Platform to enable advanced photomask designs using complex rectilinear and curvilinear shapes for superior wafer quality within practical, cost-effective write-times. D2S is the managing sponsor of the eBeam Initiative and a founding member of the Center for Deep Learning in Electronics Manufacturing (CDLe). Headquartered in San Jose, Calif., the company was founded in 2007. For more information, see: [www.design2silicon.com](http://www.design2silicon.com).

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**Contact:**

David Moreno  
Principal  
Open Sky Communications  
Tel: +1.415.519.3915  
E-mail: [dmoreno@openskypr.com](mailto:dmoreno@openskypr.com)

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